

IN THE CLAIMS

Please amend the claims as follows.

1. (Withdrawn) A method for fabrication of a light emitting device on substrate, the light emitting device having a wafer with multiple epitaxial layers and a first ohmic contact layer on the epitaxial layers remote from the substrate; the method including:
 - (a) applying to the ohmic first contact layer a seed layer of a thermally conductive metal;
 - (b) electroplating a relatively thick layer of the thermally conductive metal on the seed layer; and
 - (c) removing the substrate.
2. (Withdrawn) A method as claimed in claim 1, wherein the first ohmic contact layer is coated with an adhesion layer prior to application of the seed layer.
3. (Withdrawn) A method as claimed in claim 1, wherein the seed layer is patterned with photoresist patterns before the electroplating step (b).
4. (Withdrawn) A method as claimed in claim 3, wherein the electroplating of the relatively thick layer is between the photoresist patterns.
5. (Withdrawn) A method as claimed in claim 1, wherein between steps (b) and (c) there is performed the additional step of annealing the wafer to improve adhesion.

6. (Withdrawn) A method as claimed in claim 3 or, wherein the photoresist patterns are of a height of at least 50 micrometers, a thickness in the range of 3 to 500 micrometers, and a spacing of 300 micrometers.

7-8. (Cancelled)

9. (Withdrawn) A method as claimed in claim 1, wherein the seed layer is electroplated in step (b) without patterning, patterning being performed subsequently.

10. (Withdrawn) A method as claimed in claim 9, wherein patterning is by photoresist patterning and then wet etching, or by laser beam micro-machining of the relatively thick layer.

11. (Cancelled)

12. (Withdrawn) A method as claimed in claim 3, wherein the relatively thick layer is of a height no greater than the photoresist height, or is electroplated to a height greater than the photoresist and is subsequently thinned.

13. (Cancelled)

14. (Withdrawn) A method as claimed in claim 12, wherein thinning is by polishing.

15. (Withdrawn) A method as claimed in claim 1, wherein after step (c) there is included an extra step of forming on a second surface of the epitaxial layers a second ohmic contact layer, the second ohmic contact layer being selected from the group consisting of: opaque, transparent, and semi-transparent.

16. (Withdrawn) A method as claimed in claim 15, wherein the second ohmic contact layer is one of blank and patterned, wherein bonding pads are formed on the second ohmic contact layer.

17. (Canceled)

18. (Withdrawn) A method as claimed in claim 1, wherein after step (c) ohmic contact formation and subsequent process steps are carried out, the subsequent process steps including deposition of wire bond pads.

19. (Withdrawn) A method as claimed in claim 18, wherein the exposed epitaxial layer is cleaned and etched before the second ohmic contact layer is deposited.

20. (Withdrawn) A method as claimed in claim 15, wherein the second ohmic contact layer does not cover the whole area of the second surface of the epitaxial layers.

21. (Withdrawn) A method as claimed in claim 15, wherein after forming the second ohmic contact layer there is included testing of the light emitting devices on the wafer, and separating the wafer into individual devices.

22. (Canceled)

23. (Withdrawn) A method as claimed in claim 1, wherein the light emitting devices are fabricated without one or more selected from the group consisting of: lapping, polishing and dicing.

24. (Withdrawn) A method as claimed in claim 1, wherein the first ohmic contact layers are on p-type layers of the epitaxial layers.

25. (Withdrawn) A method as claimed in claim 15, wherein the second ohmic contact layer is formed on n-type layers of the epitaxial layers.

26. (Withdrawn) A method as claimed in claim 1, wherein after step (c), dielectric films are deposited on the epitaxial layers and openings are cut in the dielectric films and second ohmic contact layers and bond pads deposited on the epitaxial layers.

27. (Withdrawn) A method as claimed in claim 1, wherein after step (c), electroplating of a thermally conductive metal on the epitaxial layers is performed.

28. (Withdrawn) A method as claimed in claim 1, wherein the thermally conductive metal comprises copper and the epitaxial layers comprise multiple GaN-related layers.

29-30. (Canceled).

31. (Currently Amended) A light emitting device comprising:
epitaxial layers;
a first ohmic contact layer on a first surface of the epitaxial layers;
[[an]] a reflective adhesive layer on the first ohmic contact layer;
a seed layer of a thermally conductive metal on the reflective adhesive layer;
a relatively thick layer of a thermally conductive metal electroplated on the seed layer,
and a second ohmic contact layer on a second surface of the epitaxial layers, wherein the first
surface of the epitaxial layers and the second surface of the epitaxial layers are opposite surfaces.

32-33. (Canceled)

34. (Currently Amended) A light emitting device as claimed in claim 31, wherein the
relatively thick layer of the thermally conductive metal is at least 50 micrometers thick.

35. (Previously Presented) A light emitting device as claimed in claim 31, wherein the
second ohmic contact layer is a thin layer in the range of from 3 to 500 nanometers.

36. (Previously Presented) A light emitting device as claimed in claim 31, wherein the

second ohmic contact layer is selected from the group consisting of: opaque, transparent, and semi-transparent, and includes bonding pads.

37. (Cancelled)

38. (Previously Presented) A light emitting device as claimed in claim 31, wherein the thermally conductive metal is copper and the epitaxial layers comprise multiple GaN-related epitaxial layers.

39. (Previously Presented) A light emitting device as claimed in claim 31, wherein the light emitting device is selected from the group consisting of: a light emitting diode, and a laser diode.

40. (Previously Presented) A light emitting device as claimed in claim 31, wherein the first ohmic contact layer, at its interface with the epitaxial layers, is a mirror.

41. (Currently Amended) A light emitting device comprising epitaxial layers, a first ohmic contact layer on a first surface of the epitaxial layers, [[an]] a reflective adhesive layer on the first ohmic contact layer, a seed layer of a thermally conductive metal on the reflective adhesive layer, and a relatively thick layer of [[the]] a thermally conductive metal on the seed layer, and a second ohmic contact layer on a second surface of the epitaxial layers, wherein the first surface of the epitaxial layers and the second surfaces of the epitaxial layers are opposite surfaces;, and wherein the first ohmic contact layer, at its interface with the epitaxial layers, is a mirror.

42. (Currently Amended) A light emitting device as claimed in claim 41, wherein the ~~relatively thick layer of the thermally conductive metal arranged on the seed layer~~ is one or more selected from the group consisting of: a heat sink, an electrical connector, and a mechanical support.

43. (Currently Amended) A light emitting device as claimed in claim 41, ~~further comprising a second ohmic contact layer on a second surface of the epitaxial layers, wherein the second ohmic contact layer being~~ is a thin layer in the range of from 3 to 500 nanometers.

44. (Currently Amended) A light emitting device as claimed in claim 41, ~~further comprising a second ohmic contact layer,~~ wherein the second ohmic contact layer comprises bonding pads and is selected from the group consisting of: opaque, transparent, and semi-transparent.

45. (Previously Presented) A light emitting device as claimed in claim 41, wherein the thermally conductive metal comprises copper, and the epitaxial layers comprise GaN-related layers.

46. (Previously Presented) A light emitting device as claimed in claim 41, wherein the light emitting device is one of: a light emitting diode and a laser diode.

47. (Withdrawn) A method of fabrication of a light emitting device, the method including:

- (a) on a substrate with a wafer comprising multiple GaN-related epitaxial layers, forming a first ohmic contact layer on a first surface of the wafer;
- (b) removing the substrate from the wafer; and

(c) forming a second ohmic contact layer on a second surface of the wafer, the second ohmic contact layer having bonding pads formed thereon.

48. (Withdrawn) A method as claimed in claim 47, wherein the second ohmic contact layer is for light emission, and is selected from the group consisting of: opaque, transparent, and semi-transparent, the second ohmic contact layer being one of: blank, and patterned.

49. (Canceled)

50-51. (Canceled).

52. (Currently Amended) A light emitting device comprising:
multiple epitaxial layers comprising an active region;
a first surface of the multiple epitaxial layers having a first ohmic contact layer thereon;
a reflective adhesive layer on the first ohmic contact layer;
a seed layer on the ~~first ohmic contact layer~~reflective adhesive layer;
a ~~relatively thick~~ layer of a thermally conductive metal on the seed layer, the active region being close to the ~~relatively thick~~ layer for improved heat transfer; and
a second ohmic contact layer on a second surface of the epitaxial layers, wherein the first surface of the epitaxial layers and the second surface of the epitaxial layers are opposite surfaces.

53. (Currently Amended) A light emitting device as claimed in claim 52, wherein the ~~relatively thick layer of thermally conductive metal~~ is one or more selected from the group consisting of: a heat sink, an electrical connector, and a mechanical support.

54. (Currently Amended) A light emitting device as claimed in claim 52, ~~further comprising a second ohmic contact layer on a second surface of the epitaxial layers, wherein the second ohmic contact layer being~~ is a thin layer in the range of from 3 to 500 nanometers.

55. (Currently Amended) A light emitting device as claimed in claim 52, ~~further comprising a second ohmic contact layer, wherein the second ohmic contact layer comprising~~ comprises bonding pads and is selected from the group consisting of: opaque, transparent, and semi-transparent.

56. (Previously Presented) A light emitting device as claimed in claim 52, wherein the thermally conductive metal comprises copper, and the epitaxial layers comprise GaN-related layers.

57. (Previously Presented) A light emitting device as claimed in claim 52, wherein the light emitting device is one of: a light emitting diode and a laser diode.